

L Number	Hits	Search Text	DB	Time stamp
1	372378	(mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:49
2	99250	((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:56
3	380140	"3" and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:54
4	17743	((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4)) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:56
5	611	((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4)) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:57
6	50	((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4)) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:59

7	1	<p>(((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)) same ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4)))</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 07:59
8	17	<p>(((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 08:08
11	4	<p>(((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography) and 430/\$.ccls.</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 08:07

12	1	<p>((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography) and 427/\$.ccls.</p>	<p>USPAT; US-PGPUB; EPO; JPO; DERWENT</p>	<p>2004/01/20 08:07</p>
13	13	<p>((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography) not</p> <p>((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography) and 430/\$.ccls.)</p>	<p>USPAT; US-PGPUB; EPO; JPO; DERWENT</p>	<p>2004/01/20 08:10</p>

14	33	<p>(((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) not ((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography)</p>	<p>USPAT; US-PGPUB; EPO; JPO; DERWENT</p>	<p>2004/01/20 08:31</p>
20	561	<p>(((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) not ((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and lithography)</p>	<p>USPAT; US-PGPUB; EPO; JPO; DERWENT</p>	<p>2004/01/20 08:34</p>

21	31	((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) not ((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.cccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 08:40
----	----	---	---	---------------------

22	530	((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) not ((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) not ((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and (((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) not ((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and (((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 08:40
----	-----	---	---	---------------------

23	87	<p> ((((((mask\$4 or pattern\$4) and  (photosensitive or layer\$1 or resist\$1)  and (workpiece\$1 or substrate\$1)) and  ((mask\$4 or pattern\$4) same  (photosensitive or layer\$1 or resist\$1))  and ((workpiece\$1 or substrate\$1) same  (support\$4 or align\$4 or stage\$4 or mov\$4  or rotat\$4))) and ((ink\$1 or liquid\$1 or  fluid\$1) same (deposit\$4 or eject\$4 or  jet\$4 or drop\$4 or droplet\$4))) and  ((mask\$4 or pattern\$4) same  (photosensitive or layer\$1 or resist\$1))  and ((workpiece\$1 or substrate\$1) same  (stage\$4 and mov\$4 and rotat\$4))) not  ((((((mask\$4 or pattern\$4) and  (photosensitive or layer\$1 or resist\$1)  and (workpiece\$1 or substrate\$1)) and  ((mask\$4 or pattern\$4) same  (photosensitive or layer\$1 or resist\$1))  and ((workpiece\$1 or substrate\$1) same  (support\$4 or align\$4 or stage\$4 or mov\$4  or rotat\$4))) and ((ink\$1 or liquid\$1 or  fluid\$1) same (deposit\$4 or eject\$4 or  jet\$4 or drop\$4 or droplet\$4))) and  ((mask\$4 or pattern\$4) same  (photosensitive or layer\$1 or resist\$1))  and ((workpiece\$1 or substrate\$1) same  (stage\$4 and mov\$4 and rotat\$4))) and  ((mask\$4 or pattern\$4) same (negative  with (photosensitive or layer\$1 or  resist\$1))) and ((workpiece\$1 or  substrate\$1) same (stage\$4 and mov\$4 and  rotat\$4)))) not ((((((mask\$4 or  pattern\$4) and (photosensitive or layer\$1  or resist\$1) and (workpiece\$1 or  substrate\$1)) and ((mask\$4 or pattern\$4)  same (photosensitive or layer\$1 or  resist\$1)) and ((workpiece\$1 or  substrate\$1) same (support\$4 or align\$4  or stage\$4 or mov\$4 or rotat\$4))) and  (((ink\$1 or liquid\$1 or fluid\$1) same  (deposit\$4 or eject\$4 or jet\$4 or drop\$4  or droplet\$4))) and ((mask\$4 or  pattern\$4) same (photosensitive or  layer\$1 or resist\$1)) and ((workpiece\$1  or substrate\$1) same (stage\$4 and mov\$4  and rotat\$4))) not ((((((mask\$4 or  pattern\$4) and (photosensitive or layer\$1  or resist\$1) and (workpiece\$1 or  substrate\$1)) and ((mask\$4 or pattern\$4)  same (photosensitive or layer\$1 or  resist\$1)) and ((workpiece\$1 or  substrate\$1) same (support\$4 or align\$4  or stage\$4 or mov\$4 or rotat\$4))) and  (((ink\$1 or liquid\$1 or fluid\$1) same  (deposit\$4 or eject\$4 or jet\$4 or drop\$4  or droplet\$4))) and ((mask\$4 or  pattern\$4) same (photosensitive or  layer\$1 or resist\$1)) and ((workpiece\$1  or substrate\$1) same (stage\$4 and mov\$4  and rotat\$4))) and ((mask\$4 or pattern\$4)  same (negative with (photosensitive or  layer\$1 or resist\$1))) and ((workpiece\$1  or substrate\$1) same (stage\$4 and mov\$4  and rotat\$4)))) and 347/\$.ccls.)) and  427/\$.ccls. </p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 08:48
----	----	---	---	---------------------

24	13	(((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) not (((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and ((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) not (((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and (((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) not (((((((mask\$4 or pattern\$4) and (photosensitive or layer\$1 or resist\$1) and (workpiece\$1 or substrate\$1)) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (support\$4 or align\$4 or stage\$4 or mov\$4 or rotat\$4))) and (((ink\$1 or liquid\$1 or fluid\$1) same (deposit\$4 or eject\$4 or jet\$4 or drop\$4 or droplet\$4))) and ((mask\$4 or pattern\$4) same (photosensitive or layer\$1 or resist\$1)) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4))) and ((mask\$4 or pattern\$4) same (negative with (photosensitive or layer\$1 or resist\$1))) and ((workpiece\$1 or substrate\$1) same (stage\$4 and mov\$4 and rotat\$4)))) and 347/\$.ccls.)) and 250/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/20 08:48
----	----	--	---	---------------------